

## PATENT ABSTRACTS OF JAPAN

(11)Publication number : 60-075363

(43)Date of publication of application : 27.04.1985

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(51)Int.Cl.

B05D 1/28

B29C 39/10

B29C 63/22

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(21)Application number : 58-183707

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(22)Date of filing : 30.09.1983

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### (54) FORMATION OF SURFACE PROTECTIVE LAYER

#### (57)Abstract:

PURPOSE: To form a surface protective layer having excellent adhesiveness in the stage of forming the protective layer on the surface of an object by sticking a main protecting agent on a releasable base and utilizing further a dissolving or swelling agent for the main protecting agent as well as a polymn. initiator and polymn. accelerator.

CONSTITUTION: A main surface protecting agent such as natural rubber, isoprene rubber or the like is coated as a material for forming a protective film for the surface of an object on the surface of a releasable base such as PE or the like and a liquid material of a functional vinyl monomer, multifunctional vinyl monomer or functional oligomer, multifunctional oligomer or the like which dissolves or swells the main protecting agent is coated on the surface thereof. A polymn. initiator consisting of org. peroxide is incorporated on the surface coated with such liquid material or the main protective agent layer stuck directly to the object surface at 0.01W10pts.wt. by 100pts.wt. said liquid material and a polymn. accelerator is incorporated into the other one at 0.1W10pts.wt. by 100pts.wt. the liquid material, by which the liquid material is polymerized. The releasable base is finally stripped and the surface protective layer is formed on the object surface by powerful adhesion power.

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### LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other

than the examiner's decision of rejection or  
application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's  
decision of rejection]

[Date of requesting appeal against  
examiner's decision of rejection]

[Date of extinction of right]

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